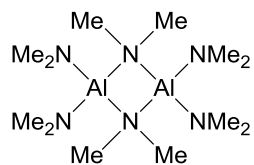


Catalog # 13-4500 Hexakis(dimethylamino)dialuminum 98% (99.9%-Al) TDMAA



Technical Notes:

1. An overlooked atomic layer deposition precursor.
2. Stoichiometric and catalytic Si-N bond formation using the p-block base TDMAA.

References:

1. *Journal of Vacuum Science & Technology, A: Vacuum, Surfaces and Films*, **2017**, 35, 01B128/1.
2. *Dalton Transactions*, **2015**, 44, 12112.